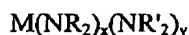


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In response to the April 13, 2004 Office Action, please amend the application as follows:

In the Claims

1. (Currently amended) A CVD precursor composition for forming a thin film dielectric on a substrate, such precursor composition including at least one metalloamide source reagent compound having a formula:



wherein M is selected from the group consisting of: Y, La, and Ta; N is nitrogen, each of R and R' is independently selected from the group consisting of H, aryl, perfluoroaryl, C₁-C₈ alkyl, C₁-C₈ perfluoroalkyl, and alkylsilyl; (NR₂)_x and (NR'₂)_y, ~~x and y~~ are different amino ligands and R' is different from R; x is from 1 to 5; y is from 1 to 5; and x+y is equal to the oxidation state of metal M.

2. (Currently amended) The CVD precursor composition according to claim 1, wherein ~~at least one of the amino ligands~~ ~~x~~ is NMe₂.

3. (Currently amended) The CVD precursor composition according to claim 1, wherein ~~at least one of the amino ligands~~ ~~x~~ is NEt₂.

4. -7 (Cancelled)

8. (Original) The CVD precursor composition according to claim 1, wherein the precursor composition further comprises a solvent medium selected from the group consisting of: ethers, glymes, tetraglymes, amines, polyamines, alcohols, glycols, aliphatic hydrocarbon solvents, aromatic hydrocarbon solvents, cyclic ethers and combinations of two or more of the foregoing.

9. (Cancelled)

10. (Previously presented) The CVD precursor composition according to claim 8, wherein the solvent is octane.

11. (Original) The CVD precursor composition according to claim 1, wherein the metalloamide source reagent compound is injected by liquid delivery into a chemical vapor deposition chamber.

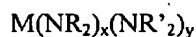
12. (Original) The CVD precursor composition according to claim 1, wherein the metalloamide source reagent compounds is delivered by bubbler into a chemical vapor deposition chamber.

13.-15. (Cancelled)

16. (Original) The CVD precursor composition according to claim 1, wherein the precursor composition comprises multiple metalloamide source reagent compounds.

17.-36. (Cancelled)

37. (Currently amended) A CVD precursor composition for forming a thin film dielectric on a substrate, such precursor composition including a vapor source reagent mixture including a metalloamide source reagent compound having a formula:



wherein M is selected from the group consisting of: Y, La, and Ta; N is nitrogen; each of R and R' is independently selected from the group consisting of H, aryl, perfluoroaryl, C₁-C₈ alkyl, C₁-C₈ perfluoroalkyl, and alkylsilyl; M(NR₂)_x and (NR'₂)_y ~~x and y~~ are different amino ligands and R' is different from R; x is from 1 to 5; y is from 1 to 5; and x+y is equal to the oxidation state of metal M.

38.-86. (Cancelled)

87. (Withdrawn) A CVD precursor composition for forming a thin film dielectric on a substrate, such precursor composition including at least one metalloamide source reagent compound having a formula:



wherein M is selected from the group consisting of: Hf, Y, La, Lanthanide series elements, and Ta; N is nitrogen each of R¹ and R² is independently selected from the group consisting of H, aryl, perfluoroaryl, C₁-C₈ alkyl, C₁-C₈ perfluoroalkyl, and alkylsilyl; x is from 1 to 5 and equal to the oxidation state of metal M.

88. (Withdrawn) The CVD precursor composition of claim 87, wherein M is Ta.

89. (Withdrawn) The CVD precursor composition of claim 87, wherein M is Y

90. (Withdrawn) The CVD precursor composition of claim 88, selected from the group consisting of Ta(NEt₂)₅, Ta(NEt₂)₅, Ta(NMeEt)₃, and Ta(NMe₂)₃.

91. (Withdrawn) The CVD precursor composition of claim 87, selected from the group consisting of Y(NMe₂)₃ and Y(NEt₂)₃.

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